

LIST OF REFERENCES CITED BY APPLICANT Form PTO-1449 (Use several sheets if necessary)				ATTY. DOCKET NO.: 4717-11500		APPLICATION NO.: 10/716,451	
				APPLICANT: Fabrice LETERTRE			
				FILING DATE: November 20, 2003		GROUP: 1765	
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*EXAMINER INITIAL	CITE NO.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
[Signature]	A1	6,328,796 B1	12/2001	Kub et al.	117	94	
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[Signature]	B2	EP 0 961 312	01/1999	EPO			
[Signature]	B3	WO 01/68957	09/2001	PCT			
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[Signature]	C1	Hugonnard-Bruyère, E., et al., "Deep Level Defectss in H ⁺ Implanted 6H-SiC Epilayers and in Silicon Carbide on Insulator Structures", <i>Materials Science and Engineering B</i> , Vol. 61-62, pp. 382-388 (1999)					
[Signature]	C2	Hugonnard-Bruyère, E., et al., "Defect Studies in Epitaxial SiC-6H Layers on Insulator (SiCOI)", <i>Microelectronic Engineering</i> , Vol. 48, pp. 277-280 (1999)					
[Signature]	C3	Müller, S.G, et al., "Progress in the Industrial Production of SiC Substrates for Semiconductor Devices", <i>Materials and Science Engineering B</i> , Vol. 80, No. 1-3, pp. 327-331 (2001)					
[Signature]	C4	Tsvetkov, V. et al., "SiC Seeded Boule Growth", <i>Materials Science Forum</i> , Vols. 264-268, pp. 3-8 (1998)					
[Signature]	C5	Tsvetkov, V.F. et al., "Recent Progress in SiC Crystal Growth", <i>Inst. Phys. Conf. Ser.</i> , No. 142, Chap. 1, pp. 17-22 (1996)					
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